

## EAST Search History

## EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2151	(174/262).CCLS.	US-PGPUB; USPAT	OR	OFF	2009/12/17 08:18
S2	262	S1 and wir\$4 layer and via	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/12/17 08:27
S3	1	("2003/0066683").URPN.	USPAT	ADJ	ON	2009/12/17 08:28
S4	14	("20030035028"   "20030058311"   "20030066683"   "20030212978"   "5098771"   "5748209"   "6161915"   "6409312"   "6431686"   "6519161"   "6805430"   "7077506"   "7138171"   "7181838"). PN. OR ("7279216"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/12/17 08:28
S5	4	("20020179331"   "20060137905"   "20080168652"   "5628852").PN. OR ("7624501").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/12/17 08:30
S6	1	("2008/0168652").URPN.	USPAT	ADJ	ON	2009/12/17 08:31
S7	2125	(29/830).CCLS.	US-PGPUB; USPAT	OR	OFF	2009/12/17 08:31
S8	318474	mask and "100"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:25
S9	2212	(174/262).CCLS.	US-PGPUB; USPAT	OR	OFF	2010/03/29 10:26
S10	460	S9 and S8	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:26
S11	35385	mask with "100"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:26

S12	70	S9 and S11	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:26
S13	107072	silicon with "100"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:28
S14	34432	silicon same ("100" with surface)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:28
S15	9	silicon same ("100" with surface) and S9	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:28
S16	5213	silicon same ("100" with surface) and lattice	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:29
S17	10	silicon same ("100" with surface) and lattice and "174".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 10:30
S18	25	("3985281"   "4994433"   "5038127"   "5071828"   "5073537"   "5231074"   "5449659"   "5741377"   "5866252"   "5968877"   "6027564").PN. OR ("6436317").URPN.	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:32
S19	2162	millor indices	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:34
S20	1	millor indices and silicon and crystal anisotropy etching	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:35
S21	5	millor and silicon and crystal anisotropy etching	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:36
S22	42	millor and silicon and crystal anisotropy etch or crystal anisotropy etching	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:37
S23	5	millor and silicon and (crystal anisotropy etch or crystal anisotropy etching)	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:37
S24	42	(crystal anisotropy etch or crystal anisotropy etching)	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:37

S25	30	("3761785"   "4485551"   "4497685"   "4584762"   "4611387"   "4649627"   "4851078"   "5258326"   "5262346"   "5296719"   "5313484").PN. OR ("5543351").URPN.	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 10:49
S26	1	("6528874").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2010/03/29 10:57
S27	0	2002-76185	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 11:26
S28	0	"200276185"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 11:27
S29	22807	process liquid	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:18
S30	2212	(174/262).CCLS.	US-PGPUB; USPAT	OR	OFF	2010/03/29 14:18
S31	6	S29 and S30	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:18
S32	0	(dissolve with seperate) and circuit board and insulat	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:20
S33	0	(dissolve with separate) and circuit board and insulat	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:20
S34	3	dissolve and separate and circuit board and insulat	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:20
S35	28573	"216".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:22
S36	158	S35 and S29	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:22

S37	24	S35 and S29 and circuit board	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:22
S38	4	circuit board and (separate with liquid) and S30	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:24
S39	67	circuit board and (separate with liquid) and "174".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:24
S40	341	circuit board and (separate with liquid) and "257".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	OFF	2010/03/29 14:27
S41	24	("5822850"   "6310391"   "6381837").PN. OR ("6528874").URPN.	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 14:27
S42	3777	metal mask and "257".clas.	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 15:04
S43	487	metal mask and "257".clas. and circuit board and silicon	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 15:04
S44	18417	mask with silicon oxide	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 15:19
S45	228	S44 and circuit board and "257".clas.	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 15:20
S46	182733	potassium hydroxide or ethylenediamine pyrocatechol or tetramethyl ammonium hydroxide	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 16:15
S47	7067	"I2" and "257".clas.	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 16:15
S48	928	S47 and circuit board	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 16:15
S49	591	(potassium hydroxide or ethylenediamine pyrocatechol or tetramethyl ammonium hydroxide) and "257".clas. and circuit board	US-PGPUB; USPAT; USOCR	ADJ	OFF	2010/03/29 16:17
S50	1	("20030190766").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2010/03/29 16:40

**EAST Search History (I nterference)**

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